

L Number	Hits	Search Text	DB	Time stamp
-	33694	etch\$4 with semiconductor with (wafer or substrate or "monocrystalline silicon")	USPAT; US-PGPUB	2004/10/19 09:54
-	97	(etch\$4 with semiconductor with (wafer or substrate or "monocrystalline silicon")) and germanium with (mask or masking or hardmask or "hard mask")	USPAT; US-PGPUB	2004/10/19 10:47
-	1083	((438/723) or (438/724)).CCLS.	USPAT; US-PGPUB	2004/10/19 10:47
-	4	((((438/723) or (438/724)).CCLS.) and (germanium with (masking or hardmask or "hard mask" or mask)).	USPAT; US-PGPUB	2004/10/19 10:48
-	4	((((438/723) or (438/724)).CCLS.) and (germanium with (masking or hardmask or "hard mask" or mask))	USPAT; US-PGPUB	2004/10/19 10:49
-	221	(etch\$4 with (silicon adj (nitride or oxide or dioxide))) and (germanium with (mask or masking or hardmask or "hard mask"))	USPAT; US-PGPUB	2004/10/19 10:50
-	3028	((438/689) or (438/704) or (438/717) or (438/723) or (438/724) or (438/945)).CCLS.	USPAT; US-PGPUB	2004/10/27 10:25
-	3	((((438/689) or (438/704) or (438/717) or (438/723) or (438/724) or (438/945)).CCLS.) and ((germanium or ge) with (hardmask or "hard mask"))	USPAT; US-PGPUB	2004/10/27 10:25